

Amendments to the Claims:

This listing of claims will replace all prior versions and listings of claims in the application:

List of Claims:

1. (currently amended) A semi-transmitting mirror-possessing substrate assembly ~~having~~ comprising:

a glass substrate[[,]];

a foundation film directly formed on said glass substrate[[,]]; and

a semi-transmitting reflective film formed on said foundation film, ~~the semi-transmitting mirror-possessing substrate characterized in that~~

wherein said foundation film ~~is made to have~~ has a thickness in a range of greater than 0 to 8 nm.

2. (currently amended) A The semi-transmitting mirror-possessing substrate assembly ~~as claimed in of~~ claim 1, ~~characterized in that~~ wherein said foundation film is made of silicon oxide (SiO_x).

3. (currently amended) A The semi-transmitting mirror-possessing substrate assembly ~~as claimed in of~~ claim 2, ~~characterized in that~~ wherein a chemical composition ratio x of oxygen (O) to silicon (Si) in the silicon oxide (SiO_x) is in a range of 1.5 to 2.0.

4. (currently amended) A The semi-transmitting mirror-possessing substrate assembly ~~as claimed in of~~ claim 1, ~~characterized in that~~ wherein said semi-transmitting reflective

film is made of at least one selected from the group consisting of Al and Al alloys.

5. (currently amended) A semi-transmitting type liquid crystal display apparatus, ~~characterized by having~~ comprising a semi-transmitting mirror-possessing substrate assembly as claimed in claim 1.

6. (currently Amended) A semi-transmitting mirror-possessing substrate assembly ~~having~~ comprising:

a glass substrate[[],];

a foundation film directly formed on said glass substrate[[],]; and

a semi-transmitting reflective film formed on said foundation film, ~~the semi-transmitting mirror-possessing substrate characterized in that~~ said foundation film is being made of silicon oxide (SiO_x) having a thickness in a range of greater than 0 to 8 nm,

wherein a chemical composition ratio x of oxygen (O) to silicon (Si) in the silicon oxide (SiO_x) is in a range of 1.5 to 2.0, and said semi-transmitting reflective film is made of at least one selected from the group consisting of Al and Al alloys.

7. (currently amended) A semi-transmitting type liquid crystal display apparatus, ~~characterized by having~~ comprising a semi-transmitting mirror-possessing substrate assembly as claimed in claim 6.